

WHAT IS CLAIMED IS:

1. A plasma CVD apparatus comprising:
a vacuum chamber;
an introducing means for introducing a gas into the vacuum chamber;
5 an exhaust means for exhausting the gas from the vacuum chamber to an outside;
an electrode for supplying an electric energy inside the vacuum chamber;
a supporting means for supporting a substrate opposing the electrode,
wherein an introducing port is located adjacent to an electrode side surface of
10 the substrate,
wherein a plurality of openings are located on a surface of the electrode opposing the substrate,
wherein the gas is exhausted from the plurality of openings to the outside of the vacuum chamber.

15 2. An apparatus according to claim 1, further comprising:
a transporting means for transporting continuously a flexible substrate.

3. An apparatus according to claim 1,
wherein each of the plurality of openings is circular,
wherein the plurality of openings are located on the surface of the electrode
20 at constant intervals.

4. An apparatus according to claim 1, wherein the electrode is a mesh-like plate.

5. A discharge electrode comprising:

two electrodes opposing each other,
wherein a plurality of openings are located on a surface of one of the two
electrodes,

wherein a gas is exhausted from the plurality of openings.

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